



PLASMASTAR series

PECVD Tool for
Solar applications

Single tube stand-alone furnace for PECVD process designed for Solar Cells Applications

The PlasmaStar PECVD System is the dedicated tool for process development on PECVD SiN processes for solar cell applications.

The PlasmaStar series handles one tube with vertical process chamber and manual or automatic loading of the graphite boat.

PlasmaStar system can be configured for processing cells up to 156x156mm pseudo and full square mono and multi-crystalline, or Ø200mm wafer.

The QUALIFLOW PECVD design is a proven system of high performance and flexible hydrogenated direct plasma, Plasma Enhanced Chemical Vapor Deposition for deposition of silicon nitride Layers. With its in-situ Plasma Etch Cleaning of the graphite electrode it will reduce maintenance manpower and down-time.



The process management control software provides full control of process recipes and easy data monitoring.

The PlasmaStar system has a limited footprint and easy access for operator loading/unloading and maintenance routines.

Main features

Cell size up to 156x156 mm and Ø200mm
Three-zone, spike and profile temperature control
Atmospheric and vacuum process capability
Up to 8 gas lines with MFCs
Horizontal laminar airflow for loading station
Process management software

Options

Gas burner or scrubber

Applications

Solar applications
MEMS
PECVD
VLSI technology

Features

Temperature range: 200°C to 600°C
Dimensions (L/W/H): 1800x750x2600 mm